

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

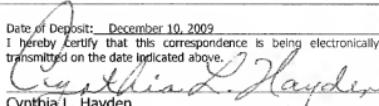
In re Applicant: § Art Unit: 2822
Chris E. Barns et al. § § Examiner: Khanh B. Duong
Serial No.: 10/629,127 § § Conf. No.: 5928
Filed: July 29, 2003 § § Docket: ITL.1016US
For: Preventing Silicide Formation at § § P16703
the Gate Electrode in a Replacement
Metal Gate Technology § § Assignee: Intel Corporation

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO DECISION ON APPEAL

Sir:

In response to the Decision on Appeal mailed October 21, 2009, please amend the above-referenced patent application as follows:


Date of Deposit: December 10, 2009
I hereby certify that this correspondence is being electronically
transmitted on the date indicated above.
Cynthia L. Hayden